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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q58716

Masayuki NAYA, et al.

Appln. No.: 09/649,013

Group Art Unit: 1756

Confirmation No.: 7581

Examiner: Martin J. Angebrannndt

Filed: August 28, 2000

For: OPTICAL WAVELENGTH CONVERTING DEVICE AND PROCESS FOR  
PRODUCING THE SAME

RECEIVED  
FEB 28 2003  
GROUP 1700

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action dated November 27, 2002, please amend the above-identified application as follows:

IN THE SPECIFICATION:

The specification is changed as follows:

Page 35, delete last paragraph, continuing on to page 36.

Examples of the resist materials, which may be employed for the second resist layer 32, include the resist materials described in U.S. Patent Nos. 5338818, 5422223, 5866306, 5385804, 5399462, 5238773, 4481049, 4689289 and 4822716; and EP No. 229629A1. Further, the resist materials shown in the following formula, which are disclosed in Japanese Unexamined Patent Publication No. 7(1995)-114188, can be employed for the second resist layer 32.

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